

NiCr

NICKEL CHROMIUM SPUTTERING TARGET

Nickel chromium sputtering target is used for thin film deposition, decoration, semiconductor, display, LED and photovoltaic devices, functional coating as nicely as other optical information storage space industry, glass coating industry like car glass and architectural glass, optical communication, etc.

Quick Facts

Product	:	Nickel Chromium Sputtering Target
Stock No	:	NS6130-10-1273
CAS	:	11106-97-1
Backing Plate	:	(As per Customer requirement)

Application

- ✓ Semiconductor
- ✓ Chemical vapor deposition (CVD)
- ✓ Physical vapor deposition (PVD) display

Additional Characteristics

Stock No.	Purity	Diameter	Thickness
NS6130-10-1273	99.99%	50.8 mm $\pm$ 1mm	3 mm $\pm$ 0.5mm

Technical Specification

Molecular Formula	Molecular Weight	Melting Point
NiCr	110.67g/mol	1400°C



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INTELLIGENT MATERIALS PVT LTD

Derabassi
Punjab (140507)
INDIA

+91 9779 550077, 9779238252

NANOSHEL UK LIMITED

Chapel House,
Chapel St Cheshire,
CW12 4AB United Kingdom

+44 (0) 74 105 488, +44 203 137 5187

NANOSHEL LLC

3422 Old Capitol Suit
1305 Wilmington DE - 19808
United States

+1 646 470 4911

ISO 9001:2015
CERTIFIED COMPANY



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20ZICE4588M

High Purity
SPUTTERING
TARGET